

SLOVENSKI STANDARD SIST EN 62047-6:2010

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Polprevodniški elementi - Mikroelektromehanski elementi - 6. del: Metode za preskušanje osne utrujenosti tankoplastnih materialov (IEC 62047-6:2009)

Semiconductor devices - Micro-electromechanical devices - Part 6: Axial fatigue testing methods of thin film materials (IEC 62047-6:2009)

Halbleiterbauelemente - Bauelemente der Mikrosystemtechnik - Teil 6: Prüfverfahren zur uniaxialen Dauerschwingfestigkeit von Dünnschicht-Werkstoffen (IEC 62047-6:2009)

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Dispositifs à semiconducteurs - Dispositifs micro-électromécaniques - Partie 6: Méthodes d'essais de fatigue axiale des matériaux en couche (CEI 62047-6:2009)

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EUROPEAN STANDARD

EN 62047-6

NORME EUROPÉENNE EUROPÄISCHE NORM

March 2010

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English version

Semiconductor devices Micro-electromechanical devices Part 6: Axial fatigue testing methods of thin film materials (IEC 62047-6:2009)

Dispositifs à semiconducteurs -Dispositifs microélectromécaniques -Partie 6: Méthodes d'essais de fatigue axiale des matériaux en couche mince

(CEI 62047-6:2009)

Halbleiterbauelemente -Bauelemente der Mikrosystemtechnik -Teil 6: Prüfverfahren zur uniaxialen Dauerschwingfestigkeit von Dünnschicht-Werkstoffen (IEC 62047-6:2009)

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Up-to-date lists and bibliographical references concerning such national standards may be obtained on application to the Central Secretariat or to any CENELEC member.

This European Standard exists in three official versions (English, French, German). A version in any other language made by translation under the responsibility of a CENELEC member into its own language and notified to the Central Secretariat has the same status as the official versions.

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CENELEC

European Committee for Electrotechnical Standardization Comité Européen de Normalisation Electrotechnique Europäisches Komitee für Elektrotechnische Normung

Central Secretariat: Avenue Marnix 17, B - 1000 Brussels

Foreword

The text of document 47F/15/FDIS, future edition 1 of IEC 62047-6, prepared by SC 47F, Micro-electromechanical systems, of IEC TC 47, Semiconductor devices, was submitted to the IEC-CENELEC parallel vote and was approved by CENELEC as EN 62047-6 on 2010-03-01.

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The following dates were fixed:

 latest date by which the EN has to be implemented at national level by publication of an identical national standard or by endorsement

(dop) 2010-12-01

 latest date by which the national standards conflicting with the EN have to be withdrawn

(dow) 2013-03-01

Annex ZA has been added by CENELEC.

Endorsement notice

The text of the International Standard IEC 62047-6:2009 was approved by CENELEC as a European Standard without any modification.

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Annex ZA (normative)

Normative references to international publications with their corresponding European publications

The following referenced documents are indispensable for the application of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

NOTE When an international publication has been modified by common modifications, indicated by (mod), the relevant EN/HD applies.

PublicationYearTitleEN/HDYearIEC 62047-22006Semiconductor devices - Micro-EN 62047-22006

electromechanical devices -

Part 2: Tensile testing methods of thin film

materials

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Semiconductor devices – Micro-electromechanical devices – Part 6: Axial fatigue testing methods of thin film materials

Dispositifs à semiconducteurs <u>5</u> Dispositifs microélectromécaniques – Partie 6: Méthodes d'essais de fatigue axiale des matériaux en couche mince

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INTERNATIONAL ELECTROTECHNICAL COMMISSION

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INTERNATIONAL ELECTROTECHNICAL COMMISSION

SEMICONDUCTOR DEVICES – MICRO-ELECTROMECHANICAL DEVICES –

Part 6: Axial fatigue testing methods of thin film materials

FOREWORD

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International Standard IEC 62047-6 has been prepared by subcommittee 47F: Micro-electromechanical systems, of IEC technical committee 47: Semiconductor devices.

The text of this standard is based on the following documents:

FDIS	Report on voting
47F/15/FDIS	47F/17/RVD

Full information on the voting for the approval of this standard can be found in the report on voting indicated in the above table.

This publication has been drafted in accordance with the ISO/IEC Directives, Part 2.

A list of all the parts in the IEC 62047 series, under the general title *Semiconductor devices* – *Micro-electromechanical devices*, can be found on the IEC website.

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The committee has decided that the contents of this publication will remain unchanged until the maintenance result date indicated on the IEC web site under "http://webstore.iec.ch" in the data related to the specific publication. At this date, the publication will be

- · reconfirmed,
- withdrawn,
- · replaced by a revised edition, or
- amended.

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SEMICONDUCTOR DEVICES – MICRO-ELECTROMECHANICAL DEVICES –

Part 6: Axial fatigue testing methods of thin film materials

1 Scope

This International Standard specifies the method for axial tensile—tensile force fatigue testing of thin film materials with a length and width under 1 mm and a thickness in the range between 0,1 μ m and 10 μ m under constant force range or constant displacement range. Thin films are used as main structural materials for MEMS and micromachines.

The main structural materials for MEMS, micromachines, etc., have special features, such as typical dimensions of a few microns, material fabrication by deposition, and test piece fabrication by means of non-mechanical machining, including photolithography. This International Standard specifies the axial force fatigue testing methods for micro-sized smooth specimens, which enables a guarantee of accuracy corresponding to the special features. The tests are carried out at room temperatures, in air, with loading applied to the test piece along the longitudinal axis.

2 Normative references

The following referenced documents are indispensable for the application of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

IEC 62047-2:2006, Semiconductor devices 6204Micro-electromechanical devices – Part 2: Tensile testing method/ofathindfilm/materialsandards/sist/cf9d2503-83dd-4159-a5a1-

45ccc2c9d326/sist-en-62047-6-2010

3 Terms and definitions

For the purposes of this document, the following terms and definitions apply.

3.1

maximum force

 P_{max}

highest algebraic value of applied force in a cycle

NOTE Adapted from ASTM E 1823-05a [1]1.

3.2

minimum force

 P_{min}

lowest algebraic value of applied force in a cycle

NOTE Adapted from ASTM E 1823-05a [1].

3.3

mean force

 $P_{\sf mean}$

algebraic average of the maximum and minimum forces in constant amplitude loading, or of individual cycles

NOTE Adapted from ASTM E 1823-05a [1].

¹ The figures between brackets refer to the Bibliography.